

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A stage device, comprising:

a plurality of movable stages disposed on a certain movement plane so as to be movable independently of each other;

a first measurement system which measures within a predetermined measurement range a position of one of the plurality of movable stages; and

a second measurement system which measures an amount of positional deviation of each of the plurality of movable stages from a predetermined reference position within the predetermined measurement range, or a degree of coincidence of each of the plurality of movable stages with respect to the reference position, the second measurement system measuring the amount of positional deviation or the degree of coincidence along a first direction that is perpendicular to the certain movement plane;

wherein a measurement value obtained with the first measurement system is corrected on the basis of a measurement result of the second measurement system.
2. - 3. (Cancelled)
4. (Previously Presented) An exposure apparatus provided with the stage device according to claim 1, wherein masks on which mutually different patterns are formed are placed on the plurality of movable stages of the stage device, and the patterns of the masks on the plurality of movable stages are alternately transferred onto a substrate while being positioned.
5. (Previously Presented) An exposure apparatus provided with the stage device according to claim 1, wherein a mask is placed on a first movable stage among the plurality of movable stages of the stage device, a characteristic measurement apparatus which measures

characteristics in transfer of a pattern of the mask is placed on a second movable stage of the plurality of movable stages, and the pattern of the mask is transferred onto a substrate.

6. (Previously Presented) An exposure apparatus provided with the stage device according to claim 1, wherein a substrate is placed on each of the plurality of movable stages of the stage device, and the plurality of substrates are alternately exposed with mask patterns while the plurality of movable stages are alternately positioned at an exposure position.

7. (Previously Presented) An exposure apparatus provided with the stage device according to claim 1 and a projection optical system,

wherein a substrate is placed on a first movable stage of the plurality of movable stages of the stage device, a characteristic measurement apparatus which measures imaging characteristics of the projection optical system is placed on a second movable stage of the plurality of movable stages, and the substrate on the first movable stage is exposed with a mask pattern via the projection optical system.

8. (Previously Presented) A positioning method that makes use of the stage device according to claim 1, wherein when one of the plurality of movable stages enters the measurement range of the first measurement system, the amount of positional deviation of the one movable stage from the reference position within the measurement range, or the degree of coincidence of the one movable stage with respect to the reference position, is measured by the second measurement system, and a measurement value obtained with the first measurement system is corrected on the basis of a measurement result of the second measurement system.

9. (Cancelled)

10. (Previously Presented) A stage device comprising:

a movable stage that is movable at a predetermined degree of freedom;

an interferometer system which measures an amount of displacement of the movable stage by directing a measurement light at the movable stage and causing a reflected light thereof to interfere with a reference light, wherein the interferometer system has a plurality of measurement axes of the measurement light and is disposed such that even if one of the plurality of measurement axes is not irradiating the movable stage, the amount of displacement can still be measured by another measurement axis; and

a signal processing system with which, when the one measurement axis changes from the state of not irradiating the movable stage to a state of irradiating the movable stage, a degree of interference of the one measurement axis is estimated from a measurement result for the another measurement axis, and an initial value of the one measurement axis is set on the basis of the estimated degree of interference and a phase measured with the one measurement axis;

wherein the interferometer system measures the amount of displacement of the movable stage in the form of $f(\lambda)\{N + \Phi/(2\pi)\}$ with each of the plurality of measurement axes, where $f(\lambda)$ is a function of the wavelength λ of the measurement light, N is an integer indicating the degree of interference, and Φ is the phase.

11. (Cancelled)

12. (Original) The stage device according to Claim 10, wherein the interferometer system further has a plurality of measurement axes adjacent to each other, which measure an angle of rotation of the movable stage.

13. (Original) The stage device according to Claim 10, wherein the interferometer system is a heterodyne interference type of laser interferometer.

14. (Original) A positioning method that makes use of the stage device according to Claim 10, comprising:

estimating the phase of the one measurement axis from the measurement values of the another measurement axis in the estimation of the degree of interference of the one measurement axis from the measurement values of the other measurement axis;

comparing the estimated phase to the phase measured for the one measurement axis; and

correcting the degree of interference of the one measurement axis on the basis of this comparison result.

15. (Original) An exposure apparatus provided with the stage device according to Claim 10, which transfers a mask pattern onto a substrate, wherein the stage device is used to position the mask or the substrate.

16. (Original) A method which manufactures a device using the exposure apparatus according to Claim 4, including a step of transferring a mask pattern onto a substrate using the exposure apparatus.

17. - 20. (Cancelled)

21. (Original) A method which manufactures a device using the exposure apparatus according to Claim 5, including a step of transferring a mask pattern onto a substrate using the exposure apparatus.

22. (Original) A method which manufactures a device using the exposure apparatus according to Claim 6, including a step of transferring a mask pattern onto a substrate using the exposure apparatus.

23. (Original) A method which manufactures a device using the exposure apparatus according to Claim 7, including a step of transferring a mask pattern onto a substrate using the exposure apparatus.

24. (Original) A method which manufactures a device using the exposure apparatus according to Claim 15, including a step of transferring a mask pattern onto a substrate using the exposure apparatus.

25. - 34. (Cancelled)

35. (Currently Amended) A scanning exposure apparatus, comprising:

a reticle stage which is movable and holds a mask having a pattern;

~~first and second movable stages disposed in a certain movement plane so as to be movable independently of each other, the first movable stage holding a first substrate and the second movable stage holding a second substrate;~~

a first movable stage disposed in a certain movement plane, the first movable stage holding a first substrate on a first holding surface and having a first reflective member on a first side surface of the first movable stage which is perpendicular to the first holding surface;

a second movable stage disposed in the certain movement plane so as to be movable independently from the first movable stage, the second movable stage holding a second substrate on a second holding surface and having a second reflective member on a second side surface of the second movable stage which is perpendicular to the second holding surface;

a scanning system which scans one of the first and second movable stages and the reticle stage along a scanning axis;

a first measurement system which measures within a first measurement range a position of one of the first and second movable stages, the first measurement system being capable of emitting a measurement beam to a mirror of each of the first and second movable stages;

a second measurement system which measures positions of the first and second movable stages within a second measurement range partially overlapping the first measurement range; and

a control system which corrects measurement results of the first and second measurement systems on the basis of the measurement results of the first and second measurement systems.

36. (Previously Presented) The scanning exposure apparatus according to claim 35, wherein the first measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.

37. (Previously Presented) The scanning exposure apparatus according to claim 36, wherein the second measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.

38. (Previously Presented) The scanning exposure apparatus according to claim 35, wherein the second measurement system emits biaxial beams spaced apart in a direction perpendicular to the certain movement plane.

39. (Previously Presented) The scanning exposure apparatus according to claim 35, wherein the first measurement system emits the measurement beam along the scanning axis.

40. (Previously Presented) The scanning exposure apparatus according to claim 36, wherein the first measurement system emits the biaxial beams along the scanning axis.

41. (Previously Presented) The scanning exposure apparatus according to claim 37, wherein the second measurement system emits the biaxial beams along the scanning axis.

42. (Previously Presented) The scanning exposure apparatus according to claim 38, wherein the second measurement system emits the biaxial beams along the scanning axis.

43. (New) A stage device comprising:
a first movable stage having a first reflective member and a first reference mark;
a second movable stage having a second reflective member and a second reference mark;
an interferometer system which cooperates with the first and second reflective members to detect a position of the first and second movable stages alternately;
an optical sensor which detects the first and second reference marks alternately;
and
a controller which corrects an output of the interferometer system in accordance with a detection result of the optical sensor when the interferometer system detects switching between the position of the first movable stage and the position of the second movable stage.

44. (New) The stage device according to claim 43, wherein the first and second movable stages are disposed on a common base.

45. (New) The stage device according to claim 43, wherein the first reference mark is located on a first holding surface of the first movable stage and the first reflective member is provided on a first side surface perpendicular to the first holding surface.

46. (New) The stage device according to claim 45, wherein the second reference mark is located on a second holding surface of the second movable stage and the second reflective member is provided on a second side surface perpendicular to the second holding surface.